Abstract

The invention is directed to a method for the production of a surface coated with fluorine. The method according to the invention comprises the following steps:

a) a semiconductor substrate in a reaction chamber is provided;

b) the substrate surface is wetted with water and/or alcohol;

c) a fluorine-containing compound is supplied to the substrate surface so that a cleaned semiconductor surface coated with fluorine is produced;

d) the fluorine containing compound is removed from the reaction chamber; and

e) the cleaned semiconductor surface coated with fluorine is wetted with a mixture, which contains at least 10 vol % water and at least 10 vol % alcohol, so that a cleaned semiconductor surface coated with a predetermined amount of fluorine is produced.

FIG. 1